

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		10/585,245	KASAMA ET AL.	
		Examiner	Art Unit	Page 1 of 2
		MARIANNE L. PADGETT	1792	

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

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